

# EE 392B Course Introduction

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  - Digital Imaging System
  - Image Sensor Architectures
  - Nonidealities and Performance Measures
  - Color Imaging
  - Recent Developments and Trends

# Motivation

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- Image sensors are all around us:
  - Cell phones
  - Digital still and video cameras
  - Optical mice
  - Cars
  - Security cameras
  - PC and Web cameras
  - Scientific and industrial
- Digital cameras are replacing film and analog cameras for capture
- CMOS image sensors are making it possible to integrate capture and processing on the same chip, providing new capabilities for
  - Machine vision
  - Man-machine interface
  - Biometrics
  - Biological applications

- Image sensors are quite different from other types of sensors, e.g., pressure, temperature, ...
  - They comprise a massive array of detectors
  - They can detect (see) over very long distances (most other sensors are *local*)
- Several important issues beyond physics and fabrication:
  - How do we read out a very large number of signals quickly?
  - What are the *spatial* and *temporal* nonidealities that limit the performance of image sensors?
  - How do we quantify their performance?
- So, to understand image sensors, we need to use tools from several areas in EE; device physics and fabrication, optics, circuits, signals, and systems

# Course Goals

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- Provide an introduction to the design and analysis of visible range image sensors
- Develop basic understanding of the signal path through an image sensor
- Develop an understanding of the nonidealities, performance measures, and tradeoffs involved in the design of image sensors
- Discuss recent developments and future trends in this area
- The course can be used as part of an MSEE Image Systems Eng depth sequence

# Course Topics

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- Silicon photodetectors: photodiode, photogate, and pinned diode; photocurrent, quantum efficiency, and dark current; direct integration
- CCD and CMOS image sensors; architectures and readout circuits, well capacity, conversion gain, readout speed
- Image sensor technologies including color filters and microlens.
- Temporal noise
- Fixed pattern noise (FPN), DSNU, PRNU
- SNR and Dynamic range
- Spatial resolution and Modulation Transfer Function (MTF)
- Pixel optics
- High dynamic range extension schemes
- Technology scaling and modification issues

# Course Schedule

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- March 29** Overview – El Gamal.
- March 31** Photodetection in silicon, photodiode operation – El Gamal.
- April 5** Photocurrent and dark current – Wong. **HW1.**
- April 7** Photogate and direct integration – Wong.
- April 12** CCDs – Wong. **HW1 due, HW2.**
- April 14** CCDs – Wong.
- April 19** CCDs – Wong. **HW2 due, HW3.**
- April 21** CMOS image sensors – El Gamal. **Project HO.**
- April 26** CMOS image sensors – El Gamal. **HW3 due, HW4.**
- April 28** Process and layout issues. – Wong. **Project Groups due.**
- May 3** Noise analysis in circuits – El Gamal. **HW4 due, HW5.**
- May 5** Noise analysis in image sensors – El Gamal.
- May 10** Fixed pattern noise – El Gamal. **HW5 due.**
- May 12** vCam – Farrell. **Take Home Midterm.**

## Course Schedule Contd.

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**May 17** SNR and dynamic range – El Gamal. **HW6, Project information.**

**May 19** Spatial resolution, MTF – El Gamal. **Project information.**

**May 24** Pixel optics – Catrysse. **HW6 due.**

**May 26** HDR schemes.

**May 31** Course Summary. **Project Progress reports due.**

**June 7** **Projects due.**

Project format:

- We plan to propose two mini-project topics for you to choose from; one in the device and technology area and the other in the sensor design and analysis area
- The projects will be done in two-student groups
- We are open to project proposals other than the recommended ones. You need to tell us early, however

# Course Prerequisites

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- Understanding image sensors requires basic knowledge in several areas of EE
- You need to have undergraduate (preferably MSEE) level knowledge in:
  - Device physics and fabrication
  - CMOS circuits
  - Basic signals and systems
  - Optics
- We will try to be as self-contained as possible and review some of the necessary concepts and derivations
- However, depending on your background and interest, there may be some material that you will not completely understand
  - We do not expect you to have complete understanding of everything
  - As in studying any interdisciplinary field, it is more important to develop some level of understanding of *all* aspects of the field before going deeply into any particular aspect



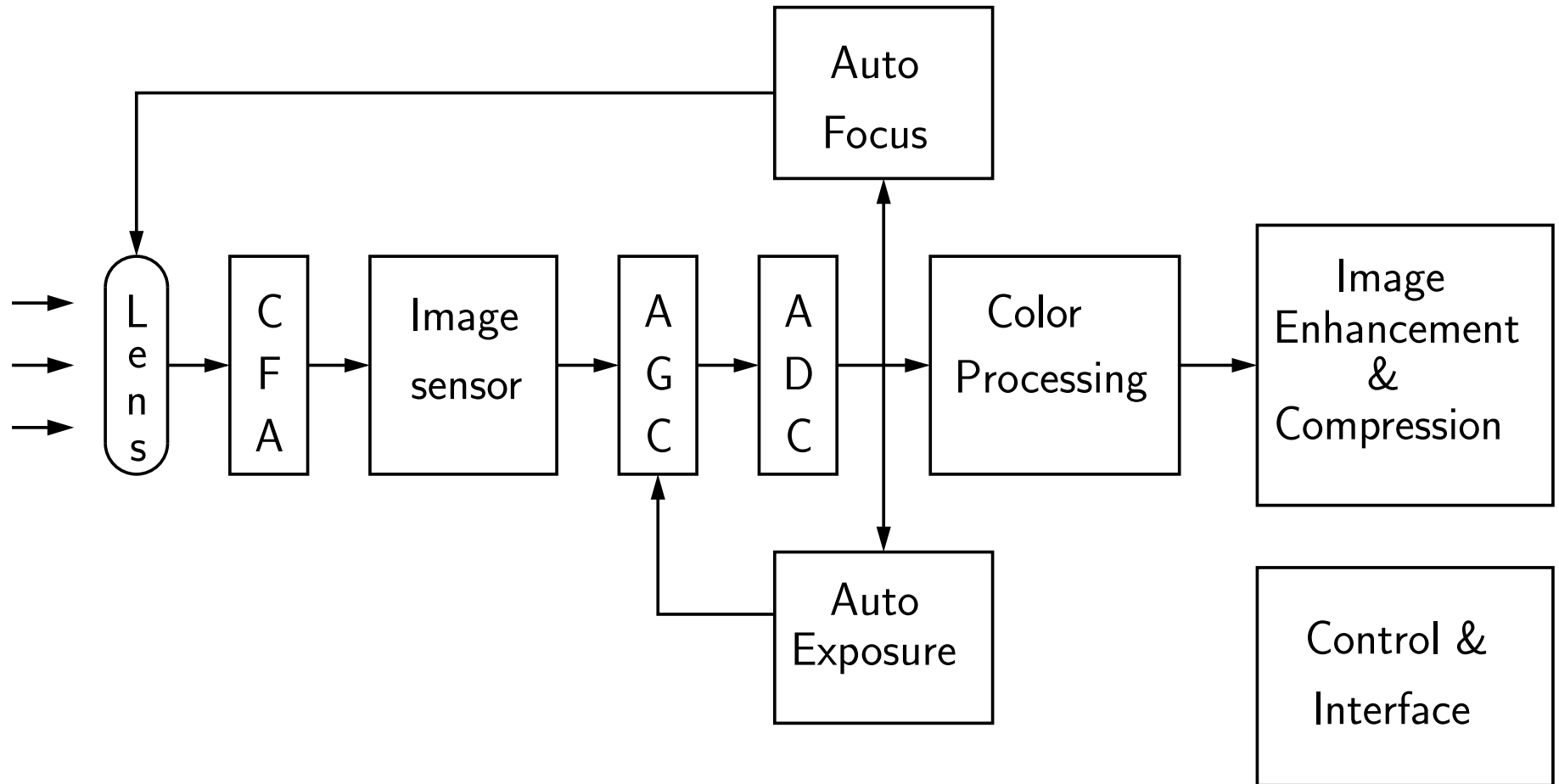
# Reading and References

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- The course has no required or recommended textbook. We will hand out lecture notes and some papers
- Here are some books that may be useful:
  - CCDs:
    - A.J.P. Theuwissen, Solid-State Imaging with Charge-Coupled Devices
    - J. D. E. Beynon, D. R. Lamb, CCD Operation, Fabrication and Limitations
  - Device physics and fabrication:
    - Muller and Kamin, Device Electronics for Integrated Circuits
    - Pierret, Semiconductor Device Fundamentals
  - Circuits:
    - A.S. Sedra and K.C. Smith, Microelectronic Circuits
    - P. Gray and R. Meyer, Analog Integrated Circuits
  - Signals and systems:
    - B.P. Lathi, Signal Processing and Linear Systems.
    - A. El Gamal, EE278 Class Notes.
- We will handout a fairly comprehensive list of references

# Digital Imaging System

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# Image Sensors

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- An area image sensor consists of:
  - An  $n \times m$  array of pixels, each comprising
    - \* a photodetector that converts incident light (photons) to photocurrent
    - \* one or more devices for readout
  - Peripheral circuits for readout and processing of pixel signals and sensor timing and control
- Sensor size ranges from  $320 \times 240$  (QVGA) for low end PC digital camera to  $7000 \times 9000$  for scientific/astronomy applications
- Pixel size ranges from  $15 \times 15 \mu\text{m}$  down to  $1.5 \times 1.5 \mu\text{m}$

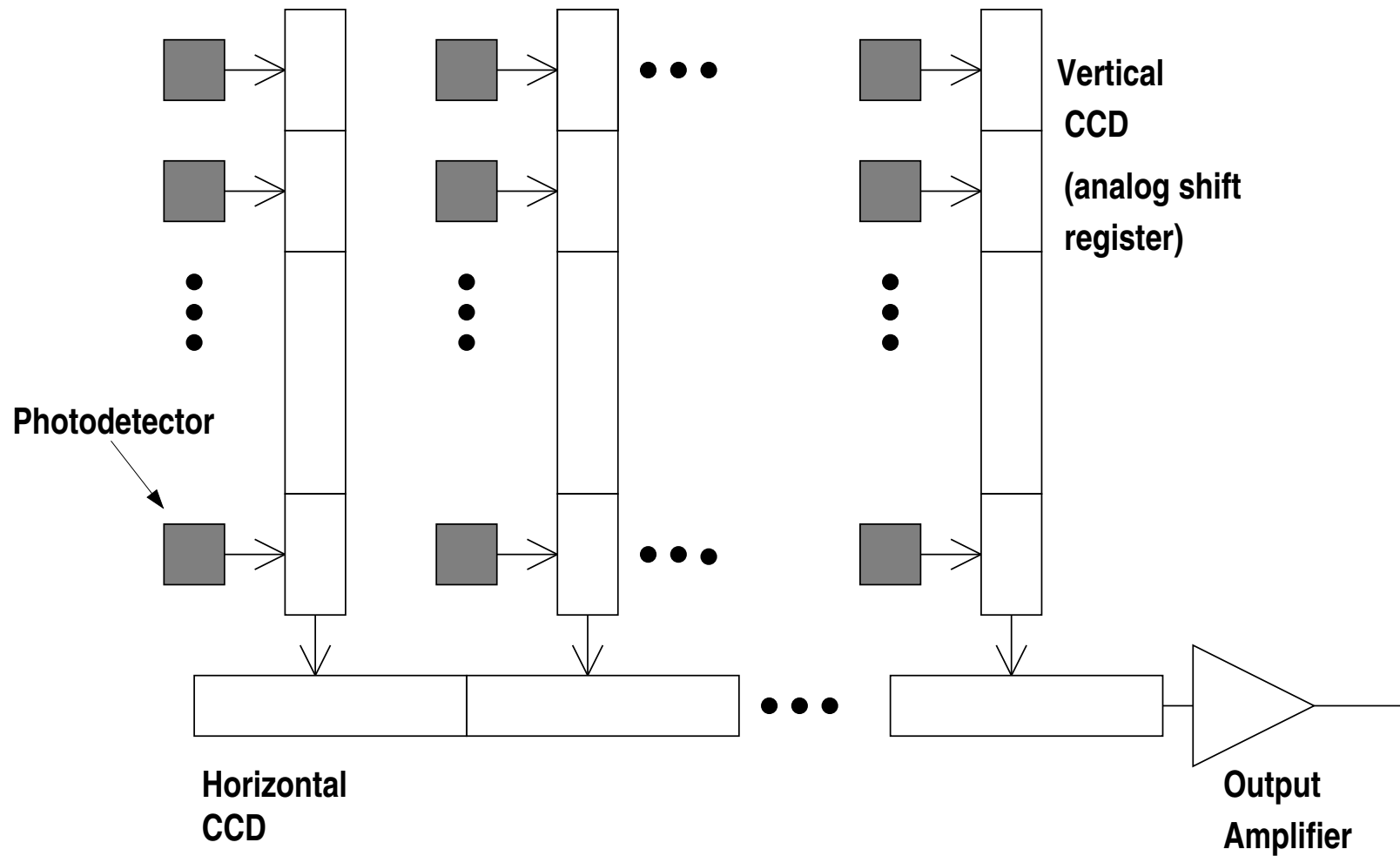
# Brief History of Image Sensors

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1965-1970	Bipolar, MOS photodiode arrays developed (Westinghouse, IBM, Plessey, Fairchild)
1970	CCD invented at Bell Labs
1970-present	CCDs dominate
1980-1985	Several MOS sensors reported
1985-1991	CMOS PPS developed (VVL)
1990s	CMOS APS developed (JPL, ...)
1994-present	CMOS DPS developed (Stanford, Pixim)
2000-present	CMOS image sensors become a commercial reality

See reference [11] of the Bibliography for more details

# CCD Image Sensors (Interline Transfer)



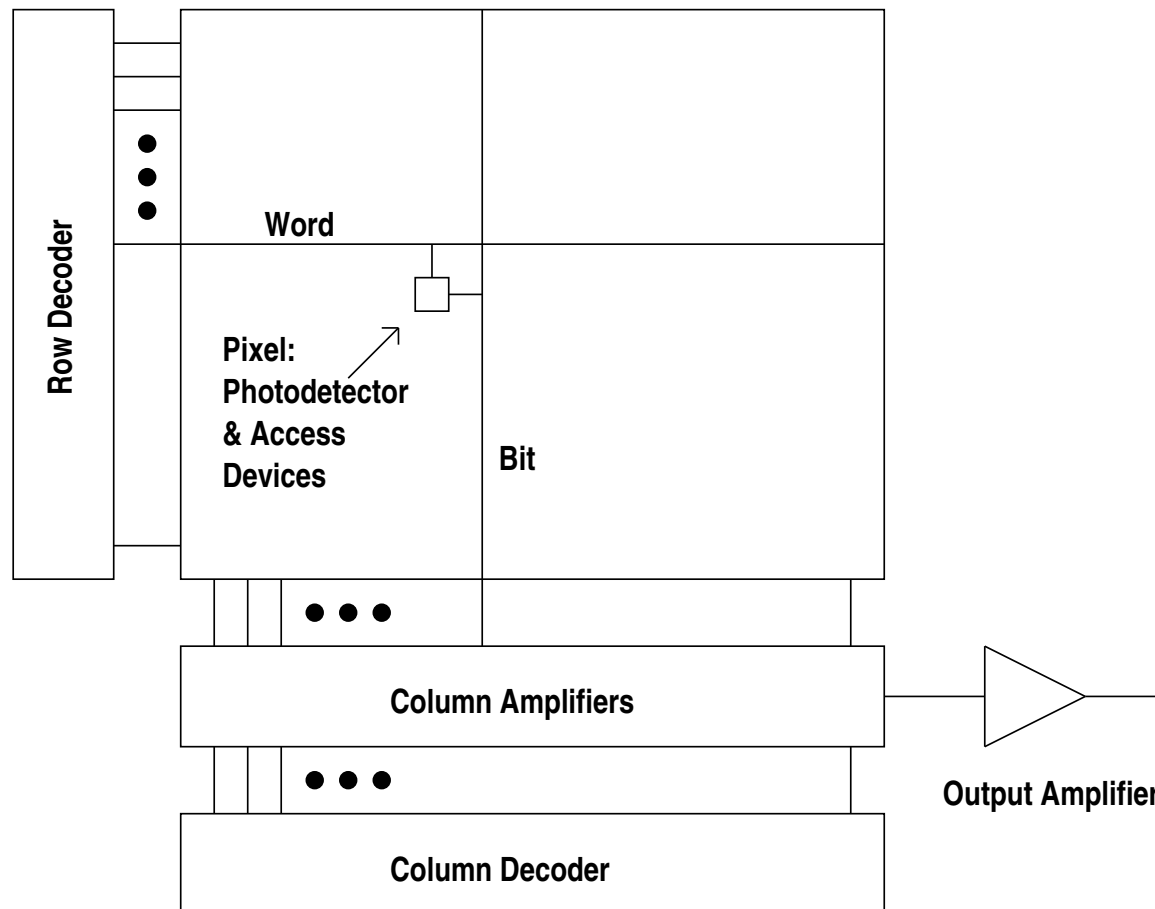
# CCD Image Sensors

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- Advantage: High quality
  - optimized photodetectors — high QE, low dark current
  - low noise and nonuniformity — CCDs do not introduce noise or cause nonuniformity
- Disadvantages:
  - difficult to integrate other camera functions on same chip
  - high power — high speed shifting clocks
  - limited frame rate — serial readout

# CMOS Image Sensors

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Most popular type called Active Pixel Sensor (APS), pixel has photodiode and 3 transistors

# CMOS Image Sensors

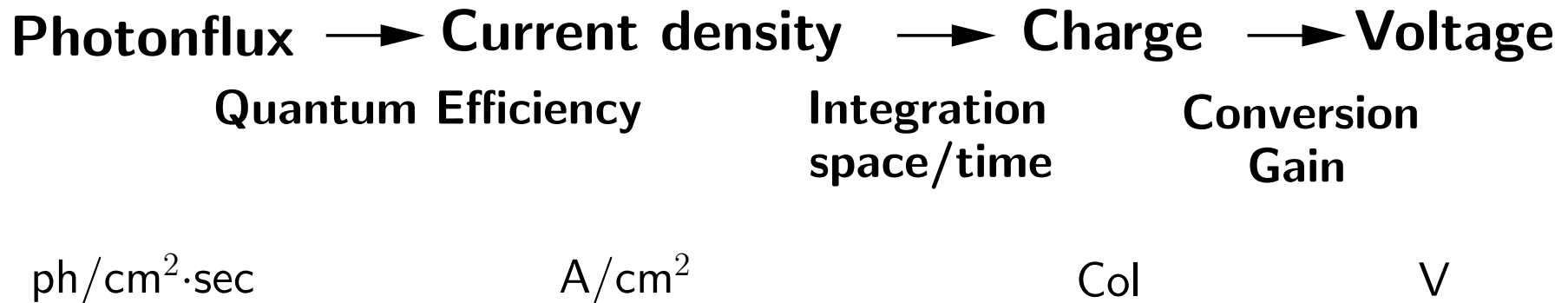
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- Advantages:
  - can integrate other camera functions on same chip
  - lower power consumption than CCDs (10X)
  - very high frame rates can be achieved
  - very high dynamic range can be achieved
- Disadvantages: lower quality at low light CCDs
  - higher dark current (CMOS process usually modified to optimize the photodetector and reduce transistor leakage, but it is still difficult to match the low dark current of CCDs)
  - lower QE (higher stack above photodetector reduces incident light)
  - high noise and nonuniformity due to multiple levels of amplification (pixel, column, and chip)



# Signal Path Through an Image Sensor

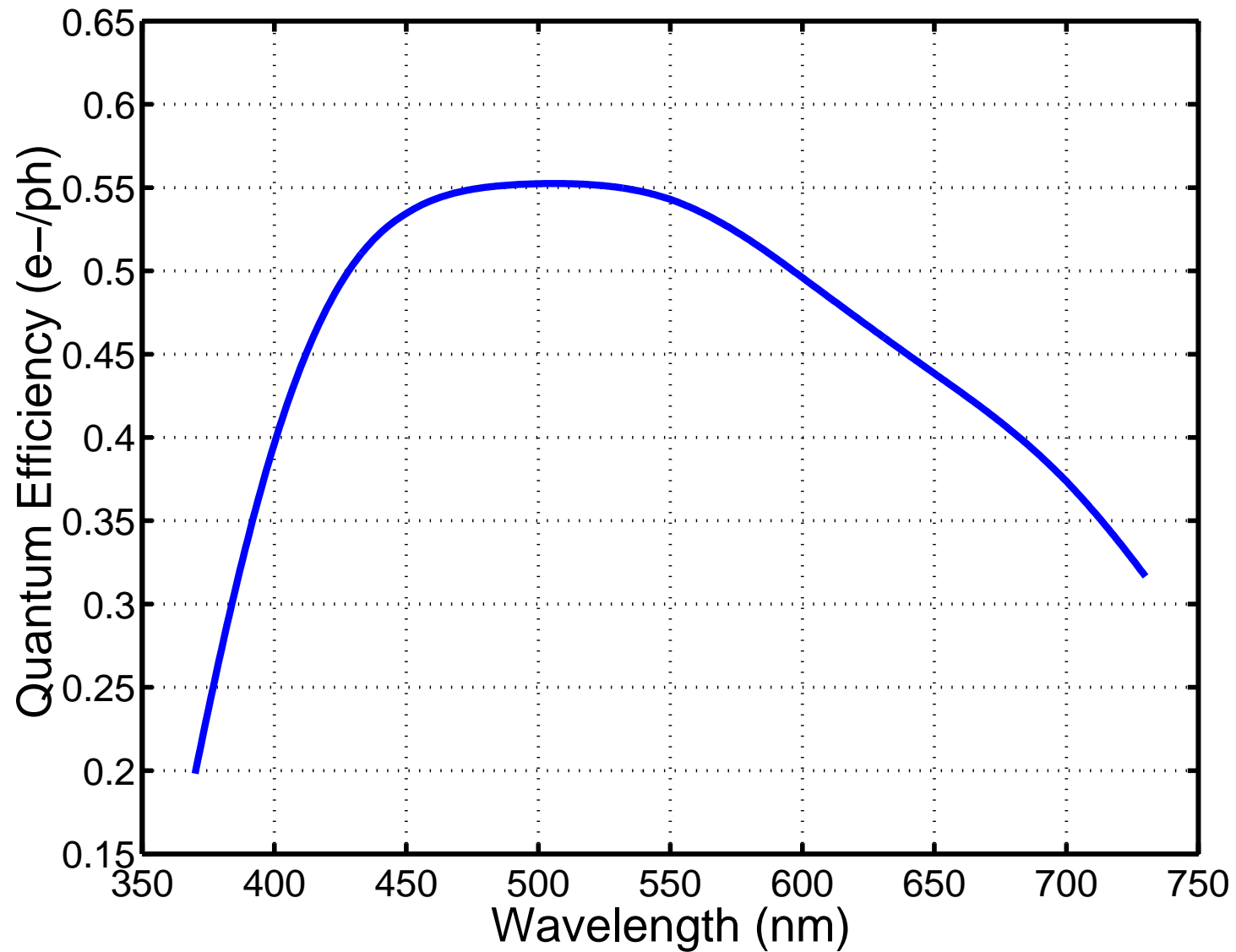
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- Quantum efficiency determined by pixel characteristics
- Due to the small photocurrent levels, the photocurrent is integrated over exposure time into charge
- Charge is converted into voltage for readout using linear amplifier(s)

# Quantum Efficiency – Example

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# Image Sensor Non-idealities

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- Temporal noise
- Fixed pattern noise (FPN)
- Dark current
- Spatial sampling and low pass filtering

# Temporal Noise

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- Caused by photodetector and MOS transistor thermal, shot, and  $1/f$  noise
- Can be lumped into two additive components:
  - Read noise
  - Integration noise (due to photodetector shot noise)
- Noise increases with signal, but so does the signal-to-noise ratio (SNR)
- Noise under dark conditions (read noise) presents a fundamental limit on sensor dynamic range (DR)

# Fixed Pattern Noise (FPN)

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- FPN (also called nonuniformity) is the spatial variation in pixel outputs under uniform illumination due to device and interconnect mismatches over the sensor
- Two FPN components: offset and gain (called Pixel Response Nonuniformity or PRNU)
- Most visible at low illumination (offset FPN more important than gain FPN)
- Worse for CMOS image sensors than for CCDs
- Offset FPN can be reduced using correlated double sampling (CDS)

# Dark current

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- Dark current is the photodetector leakage current, i.e., current not induced by photogeneration
- It limits the photodetector (and the image sensor) dynamic range
  - introduces unavoidable shot noise
  - varies substantially across the image sensor array causing *nonuniformity* (called Dark Signal Nonuniformity or DSNU) that cannot be easily removed
  - reduces signal swing

# Sampling and Low Pass Filtering

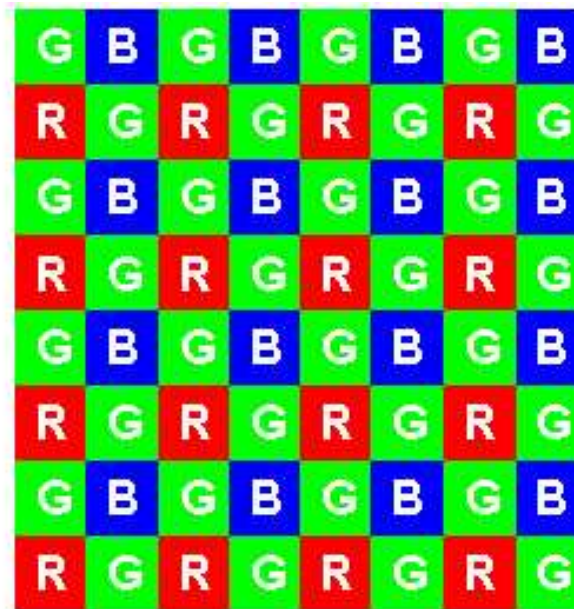
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- The image sensor is a spatial (as well as temporal) sampling device — frequency components above the Nyquist frequency cause aliasing
- It is not a point sampling device — signal low pass filtered before sampling by
  - spatial integration (of current density over photodetector area)
  - crosstalk between pixels
- Resolution below the Nyquist frequency measured by Modulation Transfer Function (MTF)
- Imaging optics also limit spatial resolution (due to diffraction)

# Color Imaging

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- To capture color images, each pixel needs to output three values (corresponding, for example, to R, G, and B)
- The most common approach is to deposit color filters on the sensor in some regular pattern, e.g., the RGB Bayer pattern

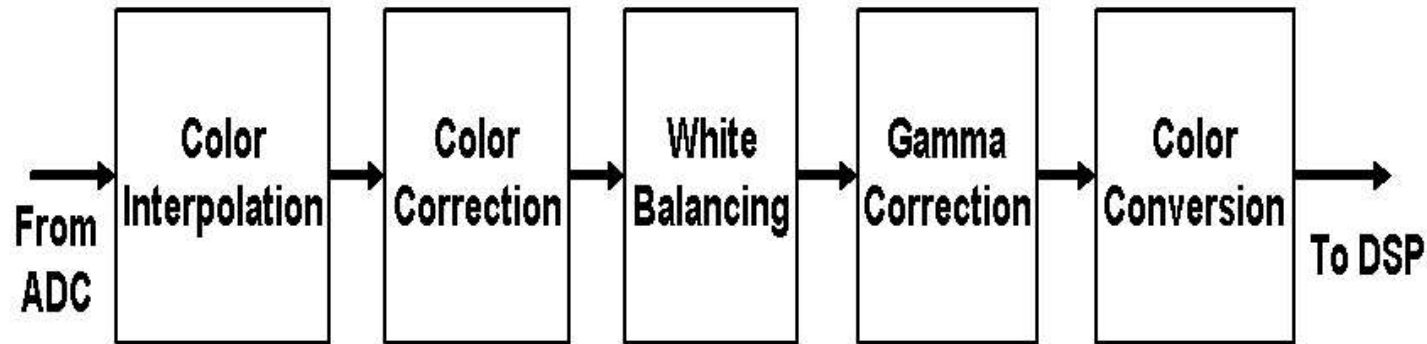


- A lot of processing is needed to obtain three colors for each pixel with the right appearance



# Color Processing

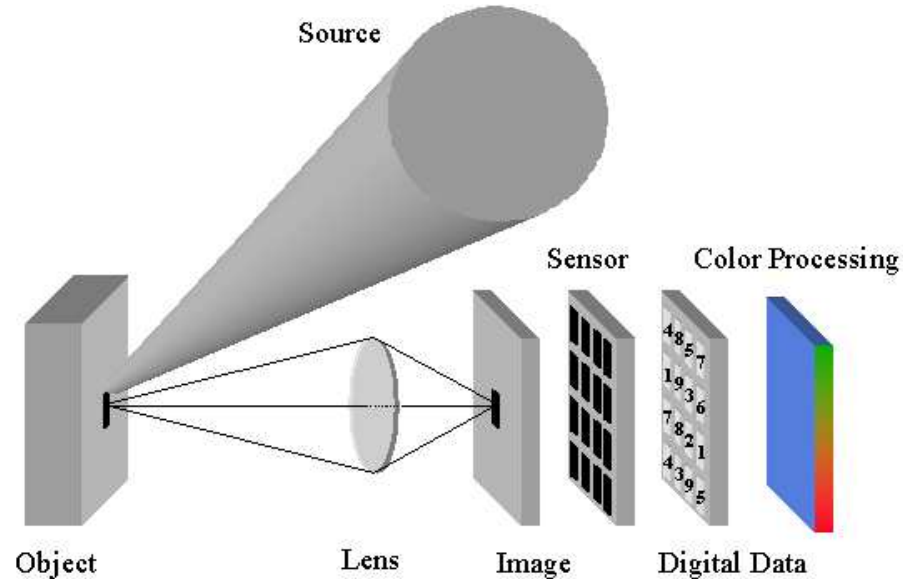
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- Interpolation used to reconstruct missing color components
- Correction and balancing used to improve appearance of color
- Gamma correction and color space conversion needed before image enhancement and compression
- Color processing very computationally demanding — over 300 MOPS needed for a  $640 \times 480$  sensor operating at 30 frames/s
- We do not discuss color processing and other digital image processing that take place in a digital camera in this course

# The vCam Camera Simulator

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- Set of MATLAB routines modeling the light source, the object, the optics, the sensor, and the ADC
- Parameters of the scene, the sensor, and the camera can be set and the corresponding output image obtained
- Allows us to visualize the effects of different sensor parameters and nonidealities
- Allows us to explore the sensor design space
- Will be used in the last homework set and in the course project

# Recent Developments and Future Trends

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- CMOS image sensor technology scaling and process modifications:
  - approach CCD quality
  - reduce pixel size
  - increase pixel counts
- Integration of image capture and processing:
  - most commercial CMOS image sensors today integrate A/D conversion, AGC, and sensor control logic on the same chip
  - some, e.g., also integrate exposure control and color processing
- Per-pixel integration is being exploited to provide new capabilities:
  - High dynamic range sensors
  - Computational sensors
  - 3D sensors
  - Lab-on-chip
- Vertical integration promises higher levels of per-pixel integration